

## PATENT ABSTRACTS OF JAPAN

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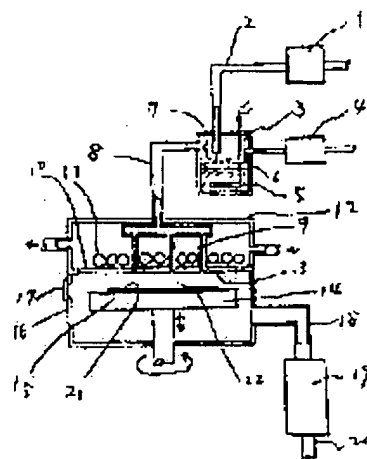
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## (54) CLEANING METHOD

## (57) Abstract:

PURPOSE: To improve the ashing removal step equalizing performance of organic matters such as a resist used as a mask for augmenting the throughput by a method wherein water or hydrogen peroxide in a gaseous state having the evaporated latent heat as well as ozone are fed onto the surface of a processed matter.

CONSTITUTION: The ozone produced by an ozone producer 1 is led in a steam feed vessel 3 through an A-piping 2. This steam feed vessel 3 is fed with pure water or hydrogen peroxide by constant quantity feeder 4 with a heater A5 built therein to maintain the constant water temperature inside the vessel 3. The steam 6 evaporated from the water level of the vessel 3 are carried by the steam 7 of ozone led in the vessel 3 is fed to multiple gas feed nozzles 9. Next, the reactive gas is fed onto the water 21 surface evenly and rapidly from the multiple gas feed nozzles 9. Accordingly, the steam 6 to be fed previously having evaporation latent heat as well as the ozone deprived of the evaporation latent heat is not cooled down by cold water at all.



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